

ABSTRACT OF THE DISCLOSURE

Relative movement occurs between the in-process substrate and the dropping section. While the substrate is rotated, the dropping section is

5 relatively moved from an approximate center of the substrate toward an outer periphery thereof. While the dropping section relatively moves from the approximate center of the in-process substrate toward the outer periphery, the rotational frequency w for the substrate

10 is decreased so that the solution film should not move due to the centrifugal force applied to a dropped solution film. Concurrently, feed rate v for the liquid from the dropping section is increased to form a solution film on the in-process substrate.

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